Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently Amended) A method for manufacturing a glass substrate for an information recording medium manufactured by polishing the surface of a raw glass plate, the method comprising:

performing a first polishing process to roughly polish the surface of the raw glass plate to form a roughly polished raw glass plate ~~be smooth~~; and

performing a second polishing process to finely polish the surface of the roughly polished raw glass plate ~~to be smoother~~;

wherein the second polishing process includes two stages:

pre-polishing with a soft polisher and a polishing agent including abrasive grains of cerium oxide; and,

post-polishing with a polishing agent including abrasive grains of silicon oxide; ~~and~~

wherein, a rinsing process is performed between the pre-polishing and the post-polishing ~~to rinse~~ comprising rinsing the raw glass plate ~~after the pre-polishing~~ with a washing liquid while sliding the raw glass plate on a surface of the soft polisher ~~to wash away the abrasive grains collected in the polishing pad in pre-polishing during the rinsing process~~.

2. (Currently Amended) The method for manufacturing a glass substrate for the information recording medium according to claim 1, wherein the abrasive grains of cerium oxide have a mean grain diameter of 1.5 μm or less and are smaller than a nap formation hole for the soft polisher ~~polishing pad~~.

3. (Currently Amended) The method for manufacturing a glass substrate for the information recording medium according to claim 2, wherein the abrasive grains of silicon oxide have a grain diameter that is smaller than the grains of cerium oxide, a mean grain diameter (D_{50}) of less than or equal to 0.2 μm, and are smaller than an ~~the~~ aperture diameter of a ~~the~~ nap formation hole for the soft polisher ~~polishing pad~~.

4. (Original) The method for manufacturing a glass substrate for the information recording medium according to claim 1, wherein the second polishing process has a total task time of 7 to 45 minutes.

5. (Original) The method for manufacturing a glass substrate for the information recording medium according to claim 1, wherein the post-polishing has a task time of 1 to 40 minutes.

6. (Original) The method for manufacturing a glass substrate for the information recording medium according to claim 1, wherein the rinsing process has a task time of 1 to 20 minutes.

7. (Currently Amended) The method for manufacturing a glass substrate for the information recording medium according to claim 1, wherein in the rinsing process, a load applied to the raw glass plate by the surface of the soft polisher ~~polishing pad~~ is lower than ~~that~~ a load applied to the raw glass plate by the surface of the soft polisher in the pre-polishing stage.

8. (Currently Amended) The method for manufacturing a glass substrate for the information recording medium according to claim 1, wherein in the rinsing process, load applied to the raw glass plate by the surface of the soft polisher ~~polishing pad~~ is the same as or lower than ~~that~~ a load applied to the raw glass plate by the surface of the soft polisher in the post-polishing stage.

9. (Currently Amended) The method for manufacturing a glass substrate for the information recording medium according to claim 1, wherein ~~load related to the rinsing process~~ a load applied to the raw glass plate by the surface of the soft polisher during the rinsing process is 25 to 70 g/cm^2.

10 - 13 (Cancelled)

14. (Currently Amended) The method for manufacturing a glass substrate for the information recording medium according to claim 1, wherein the abrasive grains of silicon oxide have a grain diameter that is smaller than the grains of cerium oxide, a mean grain diameter of less than or equal to 0.2 μm, and are smaller than an ~~the~~ aperture diameter of a nap formation hole for the soft polisher ~~polishing pad~~.

15. (Original) The method for manufacturing a glass substrate for the information recording medium according to claim 2 wherein the second polishing process has a total task time of 7 to 45 minutes.

16. (Original) The method for manufacturing a glass substrate for the information recording medium according to claim 2, wherein the post-polishing has a task time of 1 to 40 minutes.

17. (Original) The method for manufacturing a glass substrate for the information recording medium according to claim 2 wherein the rinsing process has a task time of 1 to 20 minutes.

18. (Currently Amended) The method for manufacturing a glass substrate for the information recording medium according to claim 2, wherein in the rinsing process, a load applied to the raw glass plate by the soft polisher ~~polishing pad~~ is lower than a load applied to the raw glass plate by the soft polisher ~~that~~ in the pre-polishing stage.

19. (Currently Amended) The method for manufacturing a glass substrate for the information recording medium according to claim 2, wherein in the rinsing process, load applied to the raw glass plate by the soft polisher ~~polishing pad~~ is the same as or lower than ~~that~~ a load applied to the raw glass plate by the soft polisher ~~that~~ in the post-polishing stage.

20. (Currently Amended) The method for manufacturing a glass substrate for the information recording medium according to claim 2, a load applied to the raw glass plate by the surface of the soft polisher during the rinsing process ~~wherein load related to the rinsing process~~ is 25 to 70 g/cm^2.